

SYSTEM AND METHOD OF SMOOTHING MASK SHAPES FOR IMPROVED PLACEMENT OF SUB-RESOLUTION ASSIST FEATURES

Abstract

A method is disclosed for providing associated shapes of an optical lithography mask in relation to predetermined main shapes of the mask. The method includes generating simplified layout patterns from the predetermined main shapes of the mask. Such layout patterns are generated by eliminating detail of the main shapes which leads to unmanufacturable associated shapes while preserving geometrically relevant shape information. The associated shapes are then generated relative to the simplified mask patterns.